

Notice of References Cited	Application/Control No. 09/992,560	Applicant(s)/Patent Under Reexamination GONSALVES, KENNETH E.	
	Examiner Sin J. Lee	Art Unit 1752	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-5,945,250	08-1999	Aoi et al.	430/270.1
	B	US-6,492,086 B1	12-2002	Barclay et al.	430/270.1
	C	US-			
	D	US-			
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	G	US-			
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	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N	JP 10-221852	08-1998	Japan	Aogo et al.	N/A
	O					
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	R					
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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Gonsalves et al ("High Resolution Resists for Next Generation Lithography: The Nanocomposite Approach", Materials Research Society Symposium Proceedings (2001), vol.636 (2000 Fall Meeting Proceedings (11/27/2000-12/1/2000).
	V	Chem. Abstract for JP 10-221852 (Aogo et al) - Access No. 1998:545694.
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	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.